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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
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10/616,147

07/08/2003

Klaus Kunze

KOV-004

2078

36872

7590

05/30/2008

THE LAW OFFICES OF ANDREW D. FORTNEY, PH.D., P.C.
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EXAMINER

TRINH, MICHAEL MANH

ART UNIT

PAPER NUMBER

2822

MAIL DATE

DELIVERY MODE

05/30/2008

PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary	Application No. 10/616,147	Applicant(s) KUNZE ET AL.	
	Examiner Michael Trinh	Art Unit 2822	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE ____ MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☐ Responsive to communication(s) filed on ____.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 41,43,44,46,51,53,54,56-65,96-101,103-119,121-150 and 152-205 is/are pending in the application.
- 4a) Of the above claim(s) 96-110,113-124,126-134,139-159 and 173-203 is/are withdrawn from consideration.
- 5) ☐ Claim(s) ____ is/are allowed.
- 6) ☒ Claim(s) 41,43,44,46,51,53,54,56-65,111-112,125,135-138,160-164 is/are rejected.
- 7) ☐ Claim(s) ____ is/are objected to.
- 8) ☐ Claim(s) ____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on ____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. ____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|--|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413) |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | Paper No(s)/Mail Date. ____. |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08) | 5) <input type="checkbox"/> Notice of Informal Patent Application |
| Paper No(s)/Mail Date ____. | 6) <input type="checkbox"/> Other: ____. |

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DETAILED ACTION

*** This office action is in response to Applicant's Amendment filed January 23, 2008.

Claims 41,43-44,46,51,53-54,56-65, 96-101,103-119,121-150,152-205 are pending, in which claims 96-110,113-124,126-134,139-159, 173-203 are non-elected.

*** The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.

Claim Rejections - 35 USC § 103

1. Claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shiho et al (2003/0045632) taken with Jacobson et al (both 6,294,401 and 6,200,508) and Beppu et al (5,866,471).

Shiho teaches (at paragraphs 38-93) a method for making a semiconductor film comprising at least the steps of: a) inkjet printing, offset printing, screen printing (paragraphs 110,153,54-64,162-167) a solution composition comprising passivated semiconductor nanoparticles, a first cyclic Group IVA compound of the formula Si_nR_m , n is an integer of 3 or more and m is integer of $2n+2$, wherein $\text{Si}_i\text{H}_{2n+2}$ (n is of 2 to 8), or Si_iH_{2j} (j is of 2 to 8) or Si_kH_k (k is 6,8, or 10) are mentioned at paragraphs 18,44, and a solvent (paragraphs 0102-0103,153) in a film/pattern on a substrate, wherein it may be patterned by the application of the liquid material and patterning may be carried out at the same time by an ink jet method; and b) curing said printed solution composition film/pattern to form said semiconductor film (paragraphs 117,120,137,138), wherein curing the printed pattern comprises irradiating the printed composition (paragraphs 138,113,137,120,153). Re claims 42-44, wherein the composition comprises semiconductor silicon nanoparticles (paragraphs 60-64) and passivated as the silicon particles are dispersed in the silane composition. Re claims 111-112, wherein the composition including both first and second cyclic group IVA compound of silicon and dopants of B, P, As (at paragraphs 38-93), herein $\text{Si}_n\text{H}_{2n+2}$ is mentioned at paragraph 44, wherein dopants of B, P, and As with at least alkyl group are mentioned at paragraphs 76-82. Re claims 46,58,169 wherein curing by heating so as to sintering the semiconductor film so as to dry the semiconductor film (paragraphs 117,120,137-138), wherein curing comprises irradiating the composition (paragraphs 120,138). Re claims 58-59,169-172, 125, wherein curing by heating so

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as to sintering the semiconductor film so as to dry the semiconductor film at a temperature at least about 200°C (paragraphs 117,120,137-138), wherein sintering temperature is at least about 300°C (paragraphs 117,120,137-138). Re claims 60-61, wherein the curing heat treatment is evacuated so as to treat in an inert argon gas or reducing hydrogen gas in chamber, inherently (paragraphs 117, 137). Re claim 165, wherein the formula is Si_nR_m , n is an integer of 3 or more and m is integer of $2n+2$, wherein $\text{Si}_n\text{H}_{2n+2}$ (n is of 2 to 8), or Si_jH_{2j} (j is of 2 to 8) or Si_kH_k (k is 6,8, or 10) are mentioned at paragraphs 18,44, wherein dopants of B, P, and As with at least alkyl group are mentioned at paragraphs 76-82, which is corresponding to claimed formula (1): $(\text{AH}_x)_n$, where n is from 3 to 8 and each A in the formula is independently Si, and/or a second cyclic Group IVA compound of the formula (2): $(\text{AH}_x)_m(\text{AH}_y\text{R}_z)_p(\text{ZR}')_q$, (2) where $(m+p+q)$ is from 3 to 12, each of the m instances of x is independently 0, 1 or 2, each of the p instances of y is independently 0, 1 or 2, each of the p instances of z is independently 0, 1 or 2, each of the p instances of $(y+z)$ is independently 1 or 2, each of the q instances of w is independently 0 or 1, at least one of p and q is at least 1, each A in the formula (2) is independently Si, Z is selected from the group consisting of B, P and As, R' is R or H, and each R in the formula (2) is independently alkyl, aryl, aralkyl, a halogen, $\text{BHsR}''2s$, $\text{PHsR}''2-s$, $\text{AsHR}''2-s$ or $\text{AHtR}''3-t$, where s is 0 to 2, t is 0 to 3, and R'' is alkyl, aryl, aralkyl, a halogen, or AH_3 ,

Re claims 41,166, Shiho already teaches inkjet printing a semiconductor film having a thickness, but lacks forming the semiconductor film as a patterned semiconductor film from a solution, and by gravure printing; and re further claim 166, wherein cyclogermane or cyclosilagermane is employed.

However, Jacobson '401 teaches (at col 5, lines 34-60; col 3, lines 36-65; col 4, lines 32-64) printing passivated semiconductor nanoparticles to form a patterned semiconductor film on a substrate by using any of variety including spin coating, casting, screen printing, stamping, etc, wherein the patterned semiconductor film is used in forming a thin film transistor, wherein printing is performed by ink jetting the solution composition comprising a solvent and the passivated semiconductor nanoparticles onto the substrate to form a pattern (re further claim 56, col 5, lines 34-45, col 6, lines 1-10; col 4, lines 13-15; Fig 4, col 7, lines 10-20), wherein ink-jet system is configured to deliver a selected of a series of solution, colloids, and/or dispersion of

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one or more materials, wherein the nanoparticles may be passivated at the surface by an organic capping group which is largely determined the solubility of the particles (col 4, lines 48-64), wherein by employing a screen printing process, the composition solution with the nanoparticles and the solvent is inherently deposited on the substrate through stencil on or over the substrate, and wherein the printing of the composition with solvent includes screen printing, gravure printing, lithography (re claim 57). Jacobson '508 also teaches (at Figures 1A-1C; col 2, line 31 through col 3) making a patterned semiconductor film by ink jet printing a pattern on a substrate, and curing the pattern to form the patterned semiconductor film by ink jet printing an ink having a composition solution comprising semiconductor particles having semiconductor properties such as silicon and a solvent, wherein the semiconductors may be dispersed or dissolved in an appropriate solvent. Beppu et al teach (at col 5, line 16 to col 7; col 6, lines 29-35; col 5, lines 30-35; col 7, lines 35-67, re claim 166) forming a semiconductor film by employing a semiconductor material including silicon and/or germanium, and employing a cyclic polysilane or polygermanium (cylogermane for germanium or cyclosilagermane for silicon and germanium).

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to form the semiconductor film of Shiho as a patterned semiconductor film by inkjet printing, Gravure printing, offset printing, screen printing, and spin coating a solution composition comprising passivated semiconductor nanoparticles and a solvent onto a substrate to form a pattern, as taught by Jacobson (both '401 and '508), and Shiho above, wherein by employing the ink jet printing method for forming the pattern, the passivated semiconductor nanoparticles can be dissolved/soluble or dispersed in the solvent as further taught by Jacobson (both '401 and '508), wherein forming the semiconductor film by employing silicon and/or germanium is taught by Beppu et al. This is because of the desirability to employ the ink-jet printing method or other printing processes for directly forming a plurality of patterned semiconductor films of silicon and/or germanium of a plurality of semiconductor thin film transistors, on desired and selected portions of the substrate without performing a photolithographic process for patterning, wherein by employing the ink-jetting method for depositing a pattern line, using a solution comprising passivated semiconductor nanoparticles dissolved/soluble in the solvent would effectively reduce and prevent clogging of the ink-jet

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nozzles (a commonly known problem in the ink-jet printing method). Moreover, it would have been obvious because a person of ordinary skill in the art would have been motivated to combine the prior art to achieve the claimed invention and that there would have been a reasonable expectation of success when employing a composition solution in the ink jet printing method, and because “a person of ordinary skill has a good reason to pursue the known options within his or her technical grasp. If this lead to the anticipated success, it is likely the product not of innovation but of ordinary skill and common sense” for forming a plurality of semiconductor patterns on a substrate, and because ink jet printing method is a particular known technique was recognized as part of the ordinary capabilities. In re Supreme Court Decision in KSR International Co. v. Teleflex Inc. 82 USPQ2d, 1385 (2007). This is because of the desirability to form an array of lines of patterned semiconductor films having a desired dimensions on the substrate, and for used in manufacturing a plurality of semiconductor device. The subject matter as a whole would have been obvious to one of ordinary skill in the art at the time the invention was made to select the portion of the prior art's range of value for x and n in the formula, and prior art's range of temperature, as taught by Shiho, both Jacobson, and Beppu, which is within the range of applicant's claims, because it has been held to be obvious to select a value in a known range by optimization for the best results, and would be an unpatentable modification, where the general conditions of a claim are disclosed in the prior art, it is not inventive to discover the optimum or workable ranges by routine experimentation”. *In Re Aller* 104 USPQ 233,255 (CCPA 1955); *In re Waite* 77 USPQ 586 (CCPA 1948); *In Re Swanson* 56 USPQ 372 (CCPA 1942); *In Re Sola* 25 USPQ 433 (CCPA 1935); and *In Re Dreyfus* 24 USPQ 52 (CCPA 1934).

2. Claims 51,53-54,168,204-205 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shiho et al (2003/0045632), Jacobson et al (both 6,294,401 and 6,200,508) and Beppu et al (5,866,471), as applied to claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172 above, and further of Tani et al (5,254,439).

The references including Shiho, Jacobson, and Beppu teach a method for making a semiconductor film as applied to claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172 above. Jacobson '401 teaches (at col 5, lines 34-60; col 3, lines 36-43) printing a

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composition of semiconductor nanoparticles to form a patterned semiconductor film on a substrate by using any of variety including spin coating, casting, screen printing, stamping, wherein the printing of the composition with solvent includes screen printing, gravure printing, lithography. Jacobson '508 teaches (at Figures 1A-1C; col 2, line 31 through col 3) making a patterned semiconductor film by ink jet printing a pattern on a substrate, and curing the pattern to form the patterned semiconductor film by ink jet printing an ink through a patterned aperture mask 21. Beppu et al teach (at col 5, line 16 to col 7; col 6, lines 29-35; col 5, lines 30-35; col 7, lines 35-67) forming a semiconductor film by employing a semiconductor material including silicon and/or germanium, and employing a cyclic polysilane or polygermanium (cylogermane for germanium or cyclosilagermane for silicon and germanium). Shiho also teaches (at paragraph 110) depositing the composition by inkjet printing, spray coating, spin coating, and irradiating the composition with an ultraviolet light (paragraph 138).

Shiho thus lacks selectively irradiating the composition through a mask (claims 51-54) before curing (204-205).

However, Tani teaches (at Figs 2,3; col 5, line 60 through col 6) selectively irradiating the layer through a mask aligned on substrate as marked, and removing a portion of the layer after irradiating in order to form a plurality of patterned layers.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to pattern the semiconductor film of the references including Shiho and Jacobson (both) by selectively irradiating through a mask and removing a portion of the layer as taught by Tani before curing the semiconductor film of Shiho. This is because these patterning techniques are alternative and art recognized equivalent for substitution in forming distinct patterned semiconductor films on the substrate so as a plurality of semiconductor thin film transistors can be fabricated at the same time.

3. Claims 62-65,160-164 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shiho et al (2003/0045632), Jacobson et al (both 6,294,401 and 6,200,508), and Beppu et al (5,866,471) , as applied to claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172, above, and further of Kim et al (6,355,198).

The references including Shiho, both Jacobson, and Beppu teach a method for making a semiconductor film as applied to claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172, above.

Shiho already teaches inkjet printing a semiconductor film having a thickness, particularly preferably of 0.01 to 5 μ m (paragraph 0110), while claims 62-65 and 160-164 recite an array of lines having a width of from 50nm to 50 μ m, a length of from 2 to 2000 μ m, and a thickness of from 0.01 to 500 μ m.

However, Kim teaches (at Figs 1,15,16; col 34, lines 13-50) printing and curing a composition to form an array of lines having a typical width of from 1 μ m to 10 μ m, a length of from 100 μ m, and a thickness as similar to a width and spacing of from 1 μ m to 10 μ m.

Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to form the semiconductor film of Shiho as an array of lines of a patterned semiconductor film having a typical width of from 1 μ m to 10 μ m, a length of from 100 μ m, and a thickness as similar to a width of from 1 μ m to 10 μ m by inkjet printing, gravure printing, offset printing, as taught by Kim and Shiho above. This is because of the desirability to form an array of lines of patterned semiconductor films having a desired dimensions on the substrate, and for used in manufacturing a plurality of semiconductor device. The subject matter as a whole would have been obvious to one of ordinary skill in the art at the time the invention was made to select the portion of the prior art's range of thickness, as taught by Kim and Shiho, which is within the range of applicant's claims, because it has been held to be obvious to select a value in a known range by optimization for the best results, and would be an unpatentable modification, where the general conditions of a claim are disclosed in the prior art, it is not inventive to discover the optimum or workable ranges by routine experimentation". *In Re Aller* 104 USPQ 233,255 (CCPA 1955); *In re Waite* 77 USPQ 586 (CCPA 1948); *In Re Swanson* 56 USPQ 372 (CCPA 1942); *In Re Sola* 25 USPQ 433 (CCPA 1935); and *In Re Dreyfus* 24 USPQ 52 (CCPA 1934).

4. Claims 135-138 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shiho et al (2003/0045632), Jacobson et al (both 6,294,401 and 6,200,508) and Beppu et al (5,866,471),

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as applied to claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172 above, and further of Korgel (2003/0034486) .

The references including Shiho, both Jacobson, and Beppu teach a method for making a semiconductor film as applied to claims 41,43-44,46,56-61,103-102,111-112,125,166-167,169-172, above.

Shiho already teaches (at paragraphs 0061-0062) forming silicon particles having a diameter of from 0.005 micron (5 nm as 1 micron equals to 1000nm), while claims 135-138 recites silicon particles having an average diameter of less than 5 nm or 3.5 nm.

However, Korgel teaches (at col 15, lines 12-30) forming silicon particles comprising nano-particles having an average diameter of about 5 nm, 3.5 nm, or 2 nm.

The subject matter as a whole would have been obvious to one of ordinary skill in the art at the time the invention was made to select the portion of the prior art's range of average diameter of silicon particles, as taught by Korgel, which is within the range of applicant's claims, because of the desirability to form silicon nanoparticles for forming very small devices, and because it has been held to be obvious to select a value in a known range by optimization for the best results, and would be an unpatentable modification, where the general conditions of a claim are disclosed in the prior art, it is not inventive to discover the optimum or workable ranges by routine experimentation". *In Re Aller* 104 USPQ 233,255 (CCPA 1955); *In re Waite* 77 USPQ 586 (CCPA 1948); *In Re Swanson* 56 USPQ 372 (CCPA 1942); *In Re Sola* 25 USPQ 433 (CCPA 1935); and *In Re Dreyfus* 24 USPQ 52 (CCPA 1934).

Election/Restrictions

*** As of record, Claims 96-110,113-124,126-134,139-159 are withdrawn from consideration as being directed to a non-elected invention, see 37 CFR 1.142(b). Newly submitted claims 173-203 are drawn to subject matter similar to that of non-elected claims 96-110,113-124,126-134,139-159, and accordingly be grouped into the non-elected group. Since applicant has received an action on the merits for the originally presented invention of subject matter of claim 41 as generic claim, claims 96-110,113-124,126-134,139-159, 173-203 have been constructively elected by original presentation and examination for prosecution on the merits.

Independent claim 41 is a generic claim, and being currently considered and examined with elected group. Thus, upon the allowance of a generic claim, applicant will be entitled to consideration of claims to *additional species which are written in dependent form or otherwise include all the limitations of an allowed generic claim as provided by 37 CFR 1.141*. If claims are added after the election, applicant must indicate which are readable upon the elected species. MPEP § 809.02(a).

Response to Amendment

5. Regarding prior arts:

Applicant's remarks filed January 23, 2008 with respect to pending claims have been considered but are moot in view of the new ground(s) of rejection.

Applicant remarked that "...Shiho is silent with regard to making a patterned semiconducting film by gravure printing or flexographic printing..."

In response, this is noted and found unconvincing. At least the references of Jacobson '401 clearly teaches (at col 5, lines 34-60; col 3, lines 36-65; col 4, lines 32-64) forming the patterned semiconductor film by printing passivated semiconductor nanoparticles to form a patterned semiconductor film on a substrate by using many printing techniques including ink jetting the solution composition, screen printing, gravure printing, lithography, etc..

Applicant remarked (at remark page 21+) that "...Shiho is silent with regard to...cyclogermane or cyclosilagermane..."

In response, this is noted and found unconvincing. First, claim 41 does not require of cyclogermane or cyclosilagermane. Claimed subject matter, not the specification, is the measure of invention. Limitations in the specification cannot be read into the claims for the purpose of avoiding the prior art. In *Re Self*, 213 USPQ 1,5 (CCPA 1982); In *Re Priest*, 199 USPQ 11,15 (CCPA 1978). Second, the second reference of Beppu clearly teaches (at col 5, line 16 to col 7; col 6, lines 29-35; col 5, lines 30-35; col 7, lines 35-67) forming a semiconductor film by employing a semiconductor material including silicon and/or germanium, and employing a cyclic polysilane or polygermanium (as the cyclogermane for germanium or cyclosilagermane for silicon and germanium). It is well settled that one can not show non-obviousness by attacking the references individually where, as here, the rejection is based on

combinations of references. In re Young, 403 F.2d 754,159 USPQ 725 (CCPA 1968); In re Keller 642 F.2d 413, 208 USPQ 871 (CCPA 1981). Moreover, the rejection is not overcome by pointing out that one reference does not contain a particular limitation when reliance for that teaching is on another reference. In Re Lyons 150 USPQ 741 (CCPA 1966).

As of record, Shiho clearly teaches (at paragraph 0153) that it “may be patterned by...the application of the liquid material and patterning may be carried out at the same time by an ink jet method”. Thus, by employing an ink jet method, a pattern is formed on a substrate due to the liquid materials are ink-jetted from a nozzle. Second, Jacobson teaches the desirability to directly form a pattern on a substrate by using ink-jetting or gravure printing (without performing a photolithographic process for patterning).

Shiho also clearly teaches the application of liquid material by an ink jet method. Moreover, Jacobson et al (both ‘401 and ‘508) further teach using a solution of composition in an ink jet system. Clogging of the ink-jet nozzles is effectively reduced and avoided. Moreover, it would have been obvious because a person of ordinary skill in the art would have been motivated to combine the prior art to achieve the claimed invention and that there would have been a reasonable expectation of success when employing a composition solution in the ink jet printing method, and because “a person of ordinary skill has a good reason to pursue the known options within his or her technical grasp. If this lead to the anticipated success, it is likely the product not of innovation but of ordinary skill and common sense” for forming a plurality of semiconductor patterns on a substrate, and because ink jet printing method is a particular known technique was recognized as part of the ordinary capabilities. In re Supreme Court Decision in KSR International Co. v. Teleflex Inc. 82 USPQ2d, 1385 (2007).

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event,

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however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael M. Trinh whose telephone number is (571) 272-1847. The examiner can normally be reached on M-F: 9:00 Am to 5:30 Pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on (571) 272-2429. The central fax phone number is (703) 872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Oacs-21

/Michael Trinh/

Primary Examiner, Art Unit 2822